

Title (en)
METHOD FOR PRODUCING COATED SUBSTRATES

Title (de)
VERFAHREN ZUR HERSTELLUNG VON BESCHICHTETEN SUBSTRATEN

Title (fr)
PROCÉDÉ DE FABRICATION DE SUBSTRATS REVÊTUS

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Application
EP 16714365 A 20160331

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Abstract (en)
[origin: WO2016156496A1] The invention relates to a method for producing substrates having a plasma coated surface made of a dielectric coating material in a vacuum chamber, having an AC-powered plasma device, comprising moving a substrate relative to the plasma device by means of a movement device along a curve, and depositing coating material on a surface of the substrate in a coating region along a trajectory lying on the surface of the substrate using the plasma device. Also provided is: a) the determining of actual values of a layer thickness of deposited coating material on at least parts of the trajectory in the movement direction of the substrate; b) the comparing of the actual values with target values of the layer thickness on the at least parts of the trajectory; c) the determining of parameters of the plasma device to change the amount of coating material deposited per time unit in accordance with the position of the substrate, in such a way that the actual values of the layer thickness of deposited coating material deviate by less than a predetermined difference from the target values; d) the setting of parameters of the plasma device to change the amount of coating material deposited per time unit according to point c); and e) depositing coating material by means of the plasma device, using the parameters set in point d). The invention further relates to a device for producing substrates (10, 100) having a plasma-coated surface made of a dielectric coating material in a vacuum chamber, having an AC-powered plasma device (31, 32, 150, 180), comprising a movement device for moving a substrate (10, 100) relative to the plasma device (31, 32, 150, 180) along a curve, wherein by means of the plasma device (31, 32, 150, 180) coating material is deposited on a surface (11, 101) of the substrate (10, 100) in a coating region along a trajectory lying on the surface of the substrate (12, 105), comprising a control module (140) which is designed and configured to carry out the method.

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